

2,3,5,6-Tetrafluorophenol

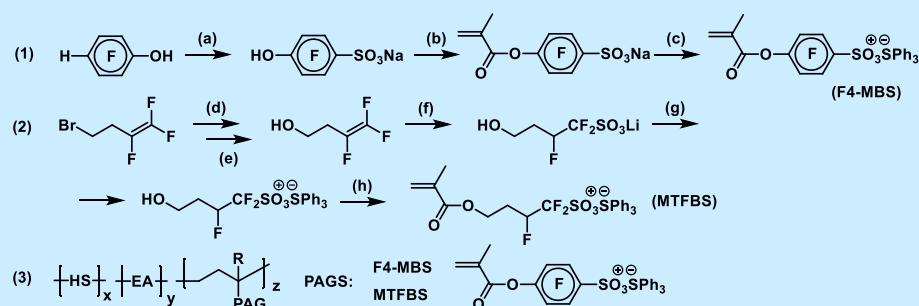
(2,3,5,6-テトラフルオロフェノール)

HC₆F₄OH

Purity	98%
CAS Number	769-39-1
Molecular Formula	C ₆ H ₂ F ₄ O
Molecular Weight	166.07

In order to improve the sensitivity and resolution of photoresists, attempts have been made to increase the resolution by introducing monomeric photoacid generators into the resist. We report on the synthesis method of monomers containing fluorinated aromatic sulfone groups and fluoroalkylsulfone groups from common raw materials, and the PEB development results of their terpolymers with hydroxystyrene (HS) and ethyl adamantyl methacrylate (EA). Although the acid generation rate of resists with photoacid-generating groups introduced into the polymer is lower than that of low-molecular-weight sulfonic acid PAGs blend resists, the resolution is good. The photoacid generation rates of the fluorinated aromatic sulfonic acid monomer (F4-MBS) and fluorinated alkyl sulfonic acid monomer (MTFBS) terpolymers were good, indicating the effect of the electron-withdrawing group of fluorine.

Application



(a) SO₃+H₂SO₄+NaCl, (b) CH₂=C(CH₃)COOH+(CF₃CO)₂O+CF₃COOH, (c) ClPPh₃, H₂O, RT, (d) CH₃COONa+CH₃COOH, (e) K₂CO₃+H₂O+MeOH, (f) SO₂+LiOH+H₂O, (g) ClPPh₃, (h) CH₂=C(CH₃)COCl

J. Fluorine Chem. 129, 2008, p607-612, *Macromolecular Rapid Communication*, 2006, 27, p1590-1595, (a) *Tetrahedron Letter*, 40, 1999, p1471-

Properties:

Appearance	Solid
Boiling point, °C	141-142
Melting point, °C	28-30
Capacity:	200kg/Month
Packing:	HDPE Jerry can